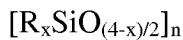


AMENDMENTS TO THE CLAIMS

The claims have been reproduced in their entirety with appropriate indications of their respective statuses.

1. (Currently Amended) A dielectric coating for use on a conductive substrate comprising:

a silicone composition silsesquioxane polymer of the formula:



wherein x=1-4 and wherein R comprises a compound selected from the group consisting of: methyl, phenyl, hydrido, hydroxyl, alkoxy groups ~~or a combination and combinations~~ of the above, or monovalent radicals independently selected from alkyl, aryl, alkylamide, arylamide, alkylamino groups ~~and or~~ arylamino radicals;

said dielectric coating having a network structure.

2. (Currently Amended) The dielectric coating of claim 1 wherein the ~~silicone composition comprises a silsesquioxane polymer compound of the formula comprises~~:



wherein R comprises a compound selected from the group consisting of: methyl, phenyl, hydrido, hydroxyl, alkoxy ~~or a combination and combinations~~ of the above or monovalent radicals independently selected from alkyl, aryl, alkylamide, arylamide, alkylamino groups ~~and or~~ arylamino radicals.

3. (Currently Amended) The dielectric coating of claim 2 wherein the silsesquioxane ~~compound polymer~~ further includes silanol units of the formula: $[RSi(OH)_xO_y]$ where $x+y=3$ and which can be silylated with appropriate organosiloxanes to produce corresponding silylated polysilsesquioxanes.

4. (Currently Amended) The dielectric coating of claim 1 wherein the ~~silicone composition silsesquioxane polymer~~ comprises a polymethyl silsesquioxane of the formula: $[CH_3SiO_{(3/2)}]_n$.

5. (Currently Amended) ~~The A dielectric coating of claim 1 wherein the silicone composition comprises for use on a conductive substrate comprising a silsesquioxane copolymer of the formula: $R^1_a R^2_b R^3_c SiO_{(4-a-b-c)/2}$, wherein: a is zero or a positive number, b is zero or a positive number, c is zero or a positive number, with the provisos that $0.8 \leq (a+b+c) \leq 3.0$ and wherein the copolymer has an average of at least two R^1 groups per molecule, and each R^1 is a functional group independently selected from the group consisting of hydrogen atoms and monovalent hydrocarbon groups having aliphatic unsaturation, and each R^2 and each R^3 are monovalent hydrocarbon groups independently selected from the group consisting of nonfunctional groups and R^1 , said dielectric coating having a network structure.~~

6. (Original) The dielectric coating of claim 5 wherein R^1 is an alkenyl group and R^2 and R^3 are nonfunctional groups selected from the group consisting of alkyl and aryl groups.

7. (Original) The dielectric coating of claim 6 wherein R^1 is selected from the group consisting of vinyl and allyl groups.

8. (Original) The dielectric coating of claim 6 wherein R^2 and R^3 are selected from the group consisting of methyl, ethyl, isopropyl, n-butyl, and isobutyl groups.

9. (Currently Amended) The dielectric coating of claim 1 wherein the ~~silicone composition silsesquioxane polymer~~ comprises a phenyl-methyl siloxane compound of the formula: $[(MeSiO_{3/2})_{0.25}(PhSiO_{3/2})_{0.15}(Ph_2SiO)_{0.10}(MePhSiO)_{0.50}]$.

10. (Currently Amended) A substrate comprising:

a flexible conductive material;

a dielectric coating disposed on a surface of the flexible conductive material;

said dielectric coating comprising a ~~silicone composition silsesquioxane polymer~~ of the formula: $[R_xSiO_{(4-x)/2}]_n$

wherein $x=1-4$ and wherein R comprises a compound selected from the group consisting of methyl, phenyl, hydrido, hydroxyl, alkoxy groups ~~or a combination and combinations~~ of the

above or monovalent radicals independently selected from alkyl, aryl, alkylamide, arylamide, alkylamino groups ~~and or~~ arylamino radicals;

said dielectric coating having a network structure.

11. (Currently Amended) The substrate of claim 10 wherein the ~~silicone composition silsesquioxane polymer~~ comprises a silsesquioxane compound of the formula:



wherein R comprises a compound selected from the group consisting of: methyl, phenyl, hydrido, hydroxyl, alkoxy ~~or a combination and combinations~~ of the above, or monovalent radicals independently selected from alkyl, aryl, alkylamide, arylamide, alkylamino groups ~~and or~~ arylamino radicals.

12. (Currently Amended) The substrate of claim 11 wherein the silsesquioxane ~~compound polymer~~ further includes silanol units of the formula:



where $x+y=3$ and which can be silylated with appropriate organosiloxanes to produce corresponding silylated polysilsesquioxanes.

13. (Currently Amended) The substrate of claim 10 wherein the ~~silicone composition silsesquioxane polymer~~ comprises a polymethyl silsesquioxane of the formula: $[\text{CH}_3\text{SiO}_{(3/2)}]_n$.

14. (Currently Amended) ~~The A substrate of claim 10 wherein the silicone composition comprises comprising a flexible conductive material, and a dielectric coating disposed on one surface of the flexible conductive material, the dielectric coating comprising a silsesquioxane~~ copolymer of the formula:



wherein: a is zero or a positive number, b is zero or a positive number, c is zero or a positive number, with the provisos that $0.8 \leq (a+b+c) \leq 3.0$ and wherein the copolymer has an average of at least 2 R^1 groups per molecule, and each R^1 is a functional group independently selected from the group consisting of hydrogen atoms and monovalent hydrocarbon groups

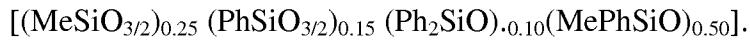
having aliphatic unsaturation, and each R² and each R³ are monovalent hydrocarbon groups independently selected from the group consisting of nonfunctional groups and R¹, said dielectric coating having a network structure.

15. (Original) The substrate of claim 14 wherein R¹ is an alkenyl group and R² and R³ are nonfunctional groups selected from the group consisting of alkyl and aryl groups.

16. (Original) The substrate of claim 15 wherein R¹ is selected from the group consisting of vinyl and allyl groups.

17. (Original) The substrate of claim 15 wherein R² and R³ are selected from the group consisting of methyl, ethyl, isopropyl, n-butyl, and isobutyl groups.

18. (Currently Amended) The substrate dielectric coating of claim 1 wherein the silicone composition silsesquioxane polymer comprises a phenyl-methyl siloxane compound of the formula:



19. (Currently Amended) The dielectric coating of claim 1, wherein the silicone composition silsesquioxane polymer further comprises a reinforcing filler.

20. (Previously Presented) The dielectric coating of claim 19, wherein the reinforcing filler comprises colloidal silica particles having a size of from 5 to 150 nm.

21. (Currently Amended) The substrate of claim 10, wherein the silicone composition silsesquioxane polymer further comprises a reinforcing filler.

22. (Previously Presented) The substrate of claim 21, wherein the reinforcing filler comprises colloidal silica particles having a size of from 5 to 150 nm.